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U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Sub-Class	Filing Date (if appropriate)
RM	4,340,456	07/1982	Robinson et al.			
	4,350,578	09/1982	Frieser et al.			
	4,528,438	07/1985	Poulsen et al.			
	5,259,888	11/1993	McCoy			
	5,314,509	05/1994	Kato et al.			
	5,269,881	12/1993	Sekiya et al.			
	5,602,061	02/1997	Fujimaki			
	5,346,578	09/1994	Benzing et al.			
	5,514,246	05/1996	Blalock			
	5,522,936	06/1996	Tamura			
RM	5,240,555	08/1993	Kilburn			

FOREIGN PATENT DOCUMENTS

Document	Date	Country	Class	Sub-class	Translation Yes/No
JP Hei 5-55184	03/1993	Japan			

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

RM	Grill, "Cold Plasma in Materials Fabrication," IEE Press, pages 99-101 (1994).
	English language Abstract of Japanese Hei 5-55184.
	Sze, "Semiconductor Devices," Wiley & Sons, pp. 341-380 (1985)
	Pierson, "Handbook of Chemical Vapor Deposition (DVD)," Noyes Publications, pp. 231-234 and 278-282 (1982).
	Hawkey's Chemical Dictionary, pp. 985, 986 and 1035.
	Sherman, "Chemical Vapor Deposition for Microelectronics," Noyes Publication, pp. 66-77 and 131-136 (1987).
RM	Dictionary of Science and Technology, W & R Chambers, pp. 495, 964, 1071 and 1254. (1974)

EXAMINER:

DATE CONSIDERED:

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication.